



IFW  
PATENT  
8007-1118

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Masaru HOSOKAWA et al.

Conf. unknown

Application No. 10/594,567

Group unknown

Filed September 27, 2006

Examiner unknown

MATERIAL FOR CHEMICAL VAPOR DEPOSITION  
AND THIN FILM FORMING METHOD

**PRELIMINARY AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

November 1, 2006

Sir:

Prior to the first Official Action on the merits,  
please amend the above-identified application as follows:

**Amendments to the Specification** begin on page 2 of this  
paper.

**Remarks** begin on page 3 of this paper.